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Patentanmeldung Nr. Patent application No. Demande de brevet n°

03079009.1

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Im Auftrag

For the President of the European Patent Office

Le Président de l'Office européen des brevets
p.o.

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Bezeichnung der Erfindung/Title of the invention/Titre de l'invention:
(Falls die Bezeichnung der Erfindung nicht angegeben ist, siehe Beschreibung.
If no title is shown please refer to the description.
Si aucun titre n'est indiqué se référer à la description.)

Method and apparatus for stabilizing a glow discharge plasma under atmospheric conditions

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Title

Method and apparatus for stabilizing a glow discharge
plasma under atmospheric conditions.

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Field of the Invention

10 The present invention relates generally to a method and an
apparatus for generating a glow discharge plasma under atmospheric
pressure conditions and, more specifically, to a method and an apparatus
for stabilizing such a glow discharge plasma.

Background of the Invention

15 Atmospheric Pressure Glow (APG) discharge is used in
practice, among others, for non-destructive material surface
modification. Glow discharge plasmas are relatively low power density
plasmas, typically generated under atmospheric pressure conditions or
partial vacuum environments.

20 Most commonly, the plasma is generated in a plasma chamber
or plasma discharge space between two oppositely arranged parallel plate
electrodes. However, the plasma may also be generated using other
electrode configurations such as, for example, adjacently arranged
electrodes. The plasma is generated in a gas or a gas mixture by
25 energizing the electrodes from AC power supply means.

It has been observed that a stable and uniform plasma can
be generated in, for example, a pure Helium or a pure Nitrogen gas.
However, as soon as impurities or other gasses or chemical compositions
at ppm level are present in the gas, the stability of the plasma will
30 decrease significantly. Typical examples of stability destroying
components are O₂, NO, CO₂, etc..

Instabilities in the plasma will either develop in a high current density plasma or will extinguish the plasma locally. With a large density of species and a high frequency of collisions in the plasma, an APG shows a fast positive feedback. That is, a random local
5 increase of the ionization of the plasma will exponentially increase. Accordingly, an instability will develop either in a high current density plasma or will extinguish locally the plasma. This phenomenon of exponential increase of the plasma current is known as glow to arc transition. As a result, current arcing occurs and the glow discharge
10 plasma can not be maintained. Instead, a combination of filamentary - and glow discharge is generated.

Filamentary discharge between parallel plate electrodes in air under atmospheric pressure has been used to generate ozone in large quantities. However, filamentary discharge is of limited use for surface
15 treatment of materials, since the plasma filaments tend to puncture or treat the surface unevenly and are associated with relatively high plasma current densities.

Summary of the Invention

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It is an object of the present invention to provide a novel and improved method and apparatus for preventing glow to arc transition in an atmospheric glow discharge plasma.

This and other objects and features are achieved, according
25 to the present invention, by a method for generating and sustaining a glow discharge plasma in a plasma discharge space comprising at least two spaced electrodes, the method comprising the steps of:

introducing in the discharge space a gas or gas mixture under atmospheric pressure conditions,

30 energizing the electrodes by applying an AC energizing voltage to the electrodes, and

controlling the energizing voltage such that at plasma generation a sharp relative decrease of a displacement current is provided.

As we are dealing with an alternating energizing voltage, the sign of the amplitude thereof and also of the displacement current will change from positive to negative. In the case of the positive half cycle or period of the energizing voltage, a decrease of the displacement current will reduce the probability of filament formation. A displacement current having a negative value will not allow the formation of any filaments. Consequently one can prevent the generation of the filaments by sharply decreasing the displacement current during the plasma generation, in accordance with the present invention.

In the case of the negative half cycle of the energizing voltage a similar explanation, but with opposite signs as mentioned above, is valid.

For clarity purposes, the term "sharp relative decrease" of the displacement current has to be construed in that the word "sharp" indicates that there is a rapid change of the displacement current, while "relative decrease" means that the sign of the changes can be positive as well as negative. In case the energizing voltage is in the positive half cycle, the "sharp relative decrease" of the displacement current means that the displacement current decreases rapidly going to zero or even a negative value. If the energizing voltage is in the negative half cycle, the "sharp relative decrease" of the displacement current means that the displacement current increases rapidly going to zero or even a positive value.

Unless it is mentioned otherwise below, the description of the processes and/or measures to stabilize the glow plasma in accordance with the invention is mainly provided for the positive half cycle of the displacement current. An identical description for the negative half cycle of the displacement current can be equally provided by changing the

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filaments. Consequently, the sharp decrease of the displacement current during the plasma generation will not affect the glow variety, but will only eliminate the risk of filament formation, as required.

The present invention is therefore most suitable for stabilizing an unstable plasma, which instability may be caused by the properties of the dielectric surface, the use of a low frequency, electron negative gas, and other factors. The method according to the present invention is also very suitable for stabilizing a plasma discharge comprising a mixture of filaments and glow, and for keeping the glow plasma stable by preventing the transition from the glow to the filamentary state.

The gas voltage variation is given by:

$$dV_{gas}/dt = dV_a/dt - I_p/C_{dielectric} \quad (1)$$

wherein: V_a = energizing or applied voltage
 V_{gas} = gas voltage
 I_p = plasma current
 $C_{dielectric}$ = capacitance of the dielectric barriers

and the first derivative of the energizing voltage or applied voltage over time is given by:

$$dV_a/dt = I_d/C \quad (2)$$

wherein: I_d = displacement current
 C = total capacitance of the dielectric barriers and discharge gap

The second derivative of the energizing or applied voltage over time is in fact proportional to the first derivative of the displacement current

over time and is given by:

$$d^2V_a/dt^2 = 1/C \cdot dI_d/dt \quad (3)$$

5 and the total current measured in the current path of the plasma electrode, I_t , is given by:

$$I_t = I_p + I_d \quad (4)$$

10 and: $V_o = V_{gas} + V_{dielectric} \quad (5)$

wherein: $V_{dielectric}$ = voltage across the dielectric barriers.

15 To avoid any instability, the gas voltage variation has to be below zero or close to zero. Thus the maximum value of the displacement current I_d^{max} has to be smaller than:

$$I_d^{max} \leq C \cdot I_p^{max}/C_{dielectric} \quad (6)$$

20 wherein: I_p^{max} = maximum value of the plasma current.

25 It will be appreciated that a small displacement current close to zero or below zero will always be below the critical stability limit, whatever the maximum plasma current density or stray or dielectric capacitance will be. Thus, by using the embodiments described in the present invention the glow will be always in a safe region wherein the glow to arc transition risk is small.

30 The method according to the present invention is also based on the insight that the adverse effects of filamentary discharge in an APG plasma for surface treatment can be reduced by enhancing or stimulating secondary electron emission from the surface by selecting a

suitable material with a relatively high secondary electron emission.

In the case that there is a tendency of a generation of local high current density instabilities (plasma filaments), the rate of filament formation is determined by the displacement current or by the time derivative of the energizing voltage. Accordingly, by controlling the second derivative over time of the energizing voltage an effective plasma stability control is achieved.

Based on the above, in a further embodiment of the invention, the displacement current is provided as a first derivative over time of an absolute value of the energizing voltage and wherein the energizing voltage is controlled in a manner such that at plasma generation the first derivative over time of the absolute value of the energizing voltage is sharply decreased.

In accordance with a preferred embodiment of the invention, at plasma generation in the positive half cycle of the energizing voltage, the displacement current is relatively decreased in fractions of a microsecond. Hence, by suddenly decreasing the first derivative over time of the absolute value of the energizing voltage, the required sharp decrease in the displacement current can be obtained both in the positive as well as the negative half cycle of the energizing voltage.

That is, with the method according to the present invention, steps are taken from the ignition of a plasma countering instabilities to occur in the plasma, that is in advance. This, different from prior art methods for stabilizing plasma currents which respond to an already occurred plasma instability, i.e. a filamentary current or streamer, as disclosed by U.S. Patent 5,414,324. For protecting the substrate or surface to be treated against sparks, i.e. current arcing in the plasma, an electrically conductive grid is provided between the electrodes. This grid is connected by an inductor having a large inductance. The grid and the inductor operate as a collector of current sparks, which already have occurred in the plasma, and are not operative

for preventing the occurrence of such sparks. That is, a spark is already present when the inductor starts to react by decreasing the energizing voltage of the plasma. Note that operation of the grid and the inductor for reducing the energizing voltage is not functional during plasma breakdown. When the plasma develops explosively at breakdown, decrease of the energizing or excitation voltage is not a guarantee that the plasma current will start to decrease. Near breakdown of the plasma, the plasma has a negative resistance, such that the current in fact will increase faster if the voltage is decreased.

In a yet further embodiment of the method according to the invention, the energizing voltage is controlled in a manner such that at plasma generation the second derivative of the energizing voltage over time is proportional and of the opposite sign to the first derivative over time of the plasma current. The stabilization of the displacement current increases significantly the uniformity of the plasma distribution over the surface to be treated, as can be seen in figure 5.

In a yet further embodiment of the method according to the invention, the dielectric material covering at least one of the electrodes should have a secondary electron emission between 0.01 and 1 and preferably between 0.1 and 1.

If the secondary electron emission is smaller than 0.01, a large volume ionisation coefficient will be required in order to keep a self sustained discharge. As a result of such a large ionisation coefficient, the discharge will develop into a streamer-like discharge. On the other hand, a stable plasma can not be generated at a secondary electron emission higher than 1.

The invention further provides a method for generating plasma, wherein the energizing voltage is controlled in a manner such that the plasma is operated at a voltage just above the breakdown voltage. Preferably, the voltage is a few percent higher than the minimum voltage needed for maintaining the plasma.

The invention provides also an apparatus for producing and sustaining a glow discharge plasma in a plasma discharge space comprising at least two spaced electrodes, means for supplying a gas or a gas mixture under atmospheric pressure conditions in the discharge space, AC power supply means for applying an energizing voltage at the electrodes, and electric stabilization means for stabilizing current variations in the plasma, characterized in that the stabilization means are arranged for controlling the energizing voltage such that at plasma generation a sharp relative decrease of the displacement current is provided. At least one of the electrodes is preferably covered by a dielectric material.

In a yet further embodiment of the apparatus according to the invention, the stabilization means are arranged for controlling the energizing voltage in a manner such that at plasma generation the relative decrease of the displacement current is provided in fractions of a microsecond. The stabilization means, comprise pulse generator means providing voltage pulses superimposed at the energizing voltage at the electrodes. The pulse generator means are controlled such to that at plasma generation the second derivate over time of the absolute value of the energizing voltage has a negative value, i.e. below zero, preferably a substantially negative value.

In another embodiment of the invention, the stabilization means are arranged for controlling the energizing voltage in a manner such that at plasma generation the second derivate of the energizing voltage over time is proportional and of the opposite sign to the first derivative over time of the plasma current.

A suitable pulse generator, for use with the present invention comprises, in an embodiment thereof, a power amplifier, having input or control terminals which are connected to means for sensing plasma current and/or means for providing the first derivative over time of the displacement current, and wherein the output terminals of the amplifier are connected in series with the power supply means and the

electrodes for superimposing a voltage pulse or voltage pulses at the plasma energizing voltage.

Means for generating the first derivative over time of the displacement current which is able to oppose the plasma current variation
5 can be provided by properly designed inductor means, such as a current choke coil incorporated in the current path of the plasma discharge space.

In an alternative embodiment of the apparatus according to the invention, the stabilization means comprise inductor means, such as
10 at least one choke coil. At least one of the electrodes and the inductor means are connected in series to the power supply means.

During breakdown of the plasma, the plasma current increases very rapidly, as a result of which a large voltage drop occurs over the inductor, which is proportional to the rate of change of the
15 current and the inductance of the inductor means. The energizing voltage applied to the plasma will show a drop having a steep slope. By a proper design of the inductor means, the second derivative over time of the absolute value of the energizing voltage will be negative during breakdown of the plasma, i.e. at the rising edge of the plasma current.

In a yet further embodiment of the invention the apparatus according to the invention comprises stabilization means having
20 electronic inductor circuitry.

From experimentally obtained data, it has been shown that the method and apparatus according to the present invention results in a
25 very stable plasma from breakdown thereof, for a variety of different supply gases, excitation conditions, electrode designs and electrode spacing, such as a distance from between 0.01 mm to 3 cm.

Gasses for generating the plasma can be selected from a group comprising Helium, Argon, Nitrogen, Air, Oxygen, Carbon Dioxide,
30 Ammonia and a mixture comprising any of the gasses of the group.

In a preferred embodiment of the invention, the gas is a

mixture of noble gas such as helium or argon and a chemically active gas such as air, oxygen and carbon dioxide. The gasses may also comprise of specific chemical compositions which are usually involved in the chemical vapour deposition processes such as SiH_4 , hydrocarbons, organosilicons such as Tetraethyl Orthosilicate (TEOS).

The apparatus and method according to the present invention can be used, in practise, for a wide variety of applications such as, but not limited to, a device for plasma surface treatment of a substrate, such as surface activation processes, which substrate can be glass, polymer, metal, etc., and for the generation of hydrophilic or hydrophobic surfaces; a plasma device for a chemical vapour deposition process; a plasma device for decomposition of gasses containing volatile organic compounds; a plasma device for removing toxical compounds from the gas phase; a plasma device for surface cleaning purposes such as in the sterilisation or dry cleaning processes.

The above-mentioned and other features and advantages of the invention are illustrated in the following description with reference to the enclosed drawings.

Brief Description of the Drawings

Fig. 1 shows, in a very schematic manner, a commonly known APG plasma device.

Fig. 2 shows a graph of the total current waveform and the energizing voltage waveform in the device of Fig. 1 in Argon, not using the present invention.

Fig. 3 shows a graph of the total current waveform and the energizing voltage waveform in the device of Fig. 1 in Argon, using the present invention.

Figs. 4 and 5 show fast camera images of surfaces treated in an APG plasma of figs. 2 and 3, respectively.

Fig. 6 shows, in a very schematic manner, an electric circuit diagram of an embodiment of the apparatus according to the present invention.

Fig. 7 shows, in a very schematic manner, an electric circuit diagram of a further embodiment of the apparatus according to the present invention.

Fig. 8 shows a graph of part of the total current waveform and the energizing voltage waveform in the apparatus of fig. 6.

Fig. 9 shows a typical I-V characteristic of an unstable plasma discharge, calculated from measured values.

Detailed Description of the Drawings

Without the intention of limitation, the present invention will now be disclosed in more detail with respect to the attached drawings. In the drawings, like parts are designated by like reference numerals.

Fig. 9 shows a typical plasma current, I_p , vs. gas voltage, V_{gas} characteristic of an unstable plasma. The gas voltage V_{gas} is depicted in Volts along the horizontal axis and is calculated by subtracting from the applied or energizing voltage V_a the voltage drop $V_{dielectric}$ across the dielectric barriers. The plasma current I_p plotted in mA along the vertical axis is calculated by subtracting the displacement current I_d from the total current I_t running through the system. The current and voltage values provided in Fig. 9 are for reference purposes only. The plasma is characterized by a very low dynamic resistance, thus being very sensitive to any perturbation.

As can be seen from Fig. 9, an increase of the gas voltage V_{gas} to values just above the breakdown voltage (i.e. near ± 1000 Volt in this example) will trigger a large plasma current variation I_p and most probably a transition from glow to arc or another filamentary state.

Fig. 1 shows a very schematic embodiment of a commonly known Atmospheric Pressure Glow (APG) plasma apparatus or device 10. The apparatus 10 comprises a plasma chamber or plasma discharge space 11 and means 12 for supplying a gas or a gas mixture under atmospheric pressure conditions in the discharge space 11, indicated by arrow 17. For producing and sustaining a glow discharge plasma in the plasma discharge space 11, for treating a surface 19 of a body 18, at least two oppositely spaced electrodes 13 and 14, in the discharge space 11 connect to AC power supply means 15, preferably AC power means, via an intermediate transformer stage 16. The frequency of said AC power supply means is selected between 10 kHz and 50 MHz.

Although two oppositely spaced electrodes 13 and 14 at a distance d are shown, the apparatus 10 may comprise a plurality of electrodes, which not necessarily have to be arranged oppositely. The electrodes 13, 14 may be positioned adjacently, for example. At least one of the electrodes is preferably covered by dielectric material having a secondary electron emission between 0.01 and 1.

In accordance with the present invention, adverse effects of filamentary discharge in an APG plasma are reduced by controlling the energizing voltage V_0 , such that at plasma generation a sharp relative decrease of the displacement current is provided, which is comes down to the case wherein the second derivate over time of the absolute value of the energizing voltage has a value less than zero, and preferably having an as large as possible negative value.

Fig. 2 shows graphically the results of the measured energizing voltage V_0 and the total current I_t waveforms in an experimental set up, wherein a plasma is created in Argon in a plasma discharge space as schematically shown in fig. 1. The electrode distance or spacing $d=1$ mm and the energizing voltage V_0 has a frequency of 11.8 kHz. Time t in microsecond is depicted running along the horizontal axis. On the left vertical axis of the graph, current values of I_t in mA are

indicated. On the right vertical axis of the graph voltage values of V_a in V are shown.

As can be seen from fig. 2, at plasma breakdown a number of current streamers is generated leading to an unwanted filamentary plasma.

5 Fig. 3 shows, similar to fig. 2, graphically the results of the measured energizing voltage V_a and the total current I_t waveforms in an experimental set up wherein a plasma is created in Argon in a plasma discharge space as schematically shown in fig. 1, however using the measures according to the present invention. The electrode distance or
10 spacing $d=1$ mm and the energizing voltage V_a has a frequency of 13 kHz.

As can be seen from fig. 3, at plasma breakdown in the positive half cycle, that is at or already before the leading edge of the total current I_t , the energizing voltage V_a is arranged to have its second derivative over time less than zero. As a result, no current
15 streamers are generated and a more uniform and stable plasma is created. The plasma is preferably generated at a voltage which is a few percent higher than the minimum voltage for maintaining the plasma.

The improvement according to the present invention can be further illustrated from pictures taken with a fast image camera of a
20 surface treated in the above-mentioned examples. Fig. 4 shows a surface treated in the set up as disclosed in connection with fig. 2. Fig. 5 shows a surface treated in the set up as disclosed in connection with fig. 3. In figs. 4 and 5, the vertical axis or direction as seen in the plane of the drawing, represents time frames of 30 microseconds and the
25 horizontal axis or direction represents spatial homogeneities of the plasma. Due to the unwanted streamers, the surface of fig. 2 is not evenly treated, which can be clearly seen from the randomly spread perturbations over the surface due to the filamentary discharge plasma generated. The surface shown in fig. 5 is clearly more evenly treated. No
30 perturbations are visible and due to a stable glow plasma generated.

In an embodiment of an apparatus 20 according to the

invention, stabilization means 21 are provided in the form of a pulse generator, indicated in dashed lines, which generates voltage pulses to modify the voltage provided by the AC power supply means 15, such that at plasma generation the second derivative over time of the energizing voltage V_0 is less than zero. The amplitude of the voltage pulses of the pulse generator 21 is opposite to the AC powering voltage of the AC power supply means 15. The pulses generated by the pulse generator 21 may be suitably superimposed on the energizing voltage.

In an alternative embodiment, the stabilization means 21 comprise a pulse generator 22 the input or control terminals 23, 24 of which are connected to current sensing means 25 which connected in series with at least one of the electrodes 13 of the plasma discharge space and the AC power supply means 15, i.e. in the total current path. The output terminals 26, 27 of the pulse generator 22 are connected in series with the power supply means 15 and the electrode 14 of the plasma discharge space.

The pulse generator 22 is activated at plasma breakdown, which is sensed by the current sensing means 25. The current sensing means 25 may take several forms, such as but not limited to electronic components, inductor means and/or a small resistor. Breakdown of the plasma can be detected from saturation of inductor means such as a choke coil, for example.

The means 25 additionally may also be arranged, in accordance with a further embodiment of the invention, for providing the first derivative over time of the displacement current dI_p/dt . Means for this purpose may comprise, inter alia, suitably designed inductor means.

In a yet further embodiment of the invention, the means 25 may be arranged for providing the first derivative over time of the energizing voltage dV_0/dt . The pulse generator means 22, at plasma generation, are arranged for suddenly decreasing dV_0/dt , generating a large and negative second derivative over time of the energizing voltage.

i.e. $d^2V_0/dt^2 \ll 0$.

Effective plasma stabilization is achieved if at plasma generation the second derivate of the voltage over time is negative, $d^2V_0/dt^2 < 0$, and its absolute value is proportional to the first derivative over time of the displacement current dI_d/dt .

Pulse generator means 22 and means 25 for current sensing and/or for providing derivatives of electric quantities are known to the skilled person and, for the purpose of the present invention, need no detailed explanation here.

Fig. 7 shows a simple embodiment of an apparatus 30 according to the invention, using inductor means 29 connected in series with the power supply means 15. The inductor means 29 may comprise suitably designed choke coil means or electronic inductor means. The inductor means are designed such to modify the supply voltage provided by the supply voltage means 15 to provide an energizing voltage V_0 at the electrodes 13, 14 having a second derivative over time less than zero.

Fig. 8 shows part of the measured energizing voltage V_0 and the total current I_t waveforms in an experimental set up, using the apparatus shown in fig. 7 with Ar gas and an electrode spacing of 1 mm.

As indicated by reference numeral 35, at the leading edge of the total current I_t , due to the operation of the inductor means 29, the energizing voltage V_0 shows a behaviour equal to a voltage of which the second derivative over time is less than zero. As a result, a very stable plasma is generated, without streamers.

Although in the above oppositely positioned electrodes have been discussed and shown in the relevant figures, the invention may also be practised with adjacently arranged electrode pairs or other configurations of electrodes of an APG apparatus.

Those skilled in the art will appreciate that many modifications and additions can be made without departing from the novel and inventive scope of the invention as defined in the appending claims.

Claims

1. Method for generating and sustaining a glow discharge plasma in a plasma discharge space comprising at least two spaced
5 electrodes, said method comprising the steps of:
introducing in said discharge space a gas or gas mixture under atmospheric pressure conditions,
energizing said electrodes by applying an AC energizing voltage to said electrodes, and
10 controlling said energizing voltage such that at plasma generation a sharp relative decrease of displacement current is provided.
2. Method according to Claim 1, wherein at least one of said electrodes is covered by a dielectric material.
3. Method according to any of the previous claims, wherein
15 said relative decrease of said displacement current is provided in fractions of a microsecond.
4. Method according to any of the previous claims, wherein said relative decrease of said displacement current is at least 100% in a fraction of a microsecond.
- 20 5. Method according to any of the previous claims, wherein at plasma generation said energizing voltage is controlled in a manner such that a second derivate of said energizing voltage over time is proportional and of opposite sign to a first derivative over time of plasma current.
- 25 6. Method according to any of the previous claims, dependent on Claim 2, wherein said dielectric material has a secondary electron emission between 0.01 and 1.
7. Method according to any of the previous claims, wherein said plasma is operated at a voltage that is a few percent higher than
30 the minimum voltage necessary for maintaining said plasma.
8. Apparatus for producing and sustaining a glow discharge

plasma in a plasma discharge space comprising at least two spaced electrodes, means for supplying a gas or a gas mixture under atmospheric pressure conditions in said discharge space, AC power supply means for applying an energizing voltage at said electrodes, and electric
5 stabilization means for stabilizing current variations in said plasma, characterized in that, said stabilization means are arranged for controlling said energizing voltage such that at plasma generation a sharp relative decrease of a displacement current is provided.

9. Apparatus according to Claim 8, wherein at plasma
10 generation said stabilization means are arranged for decreasing said displacement current to a value relatively less than a value of said displacement current before plasma breakdown.

10. Apparatus according to Claim 8 or 9, wherein said
15 stabilization means are arranged for controlling said energizing voltage in a manner such that at plasma generation said relative decrease of said displacement current is at least 100% and is provided in fractions of a microsecond.

11. Apparatus according to any of the claims 8 - 10, wherein
20 said stabilization means are arranged for providing a first derivative over time of an absolute value of said energizing voltage and for sharply decreasing said first derivative over time of said absolute value of said energizing voltage at plasma generation.

12. Apparatus according to any of the claims 8 - 11, wherein
25 said stabilization means are arranged for controlling said energizing voltage in a manner such that at plasma generation a second derivate of said energizing voltage over time is proportional and of opposite sign to a first derivative over time of plasma current.

13. Apparatus according to Claim 12, wherein said first
30 derivative of said plasma current is provided by inductor means connected in series with said electrode or electrodes of said discharge space.

14. Apparatus according to any of the claims 8 - 13, wherein

said stabilization means comprise pulse generator means providing voltage pulses superimposed at said energizing voltage at said electrodes.

15. Apparatus according to Claim 14, wherein said pulse generator is formed by a power amplifier, having input or control terminals which are connected to means for sensing plasma current, and wherein output terminals of said amplifier are connected in series with said power supply means and said electrodes for superimposing a voltage pulse at said energizing voltage.

16. Apparatus according to any of the claims 8 - 15, wherein said stabilization means comprise electronic inductor circuitry.

17. Apparatus according to any of the claims 8 - 16, wherein said electrodes are spaced over a distance of between 0.01 mm and 3 cm.

18. Apparatus according to any of the claims 8 - 17, wherein said gas is selected from a group comprising Helium, Argon, Nitrogen, Air, Oxygen, Carbon Dioxide, Ammonia and a mixture comprising any of said gasses of said group.

19. Apparatus according to any of the claims 8 - 18, wherein said gas is a mixture of a noble gas and a chemically active gas.

20. Apparatus according to any of the claims 8 - 19, wherein said AC power supply means are arranged for energizing said electrodes with an energizing voltage at a frequency between 10 kHz and 50 MHz.

21. Device for treating a surface of a substrate, comprising an apparatus according of any of the claims 8 - 20.

Abstract

Method and apparatus for generating and sustaining a glow discharge plasma in a plasma discharge space comprising at least two spaced electrodes. The method and apparatus are arranged for performing the steps of introducing in the discharge space a gas or gas mixture under atmospheric pressure conditions, energizing the electrodes by applying an AC energizing voltage (V_0) to the electrodes, and controlling the energizing voltage (V_0) such that at plasma generation a sharp relative decrease of displacement current is provided.

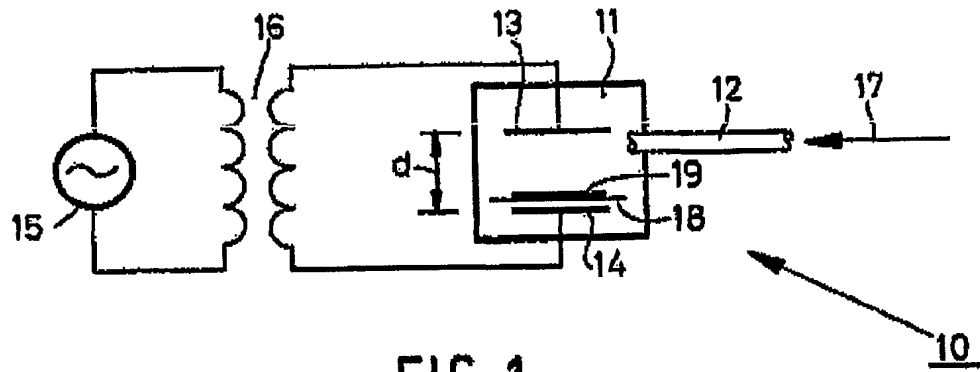


FIG. 1

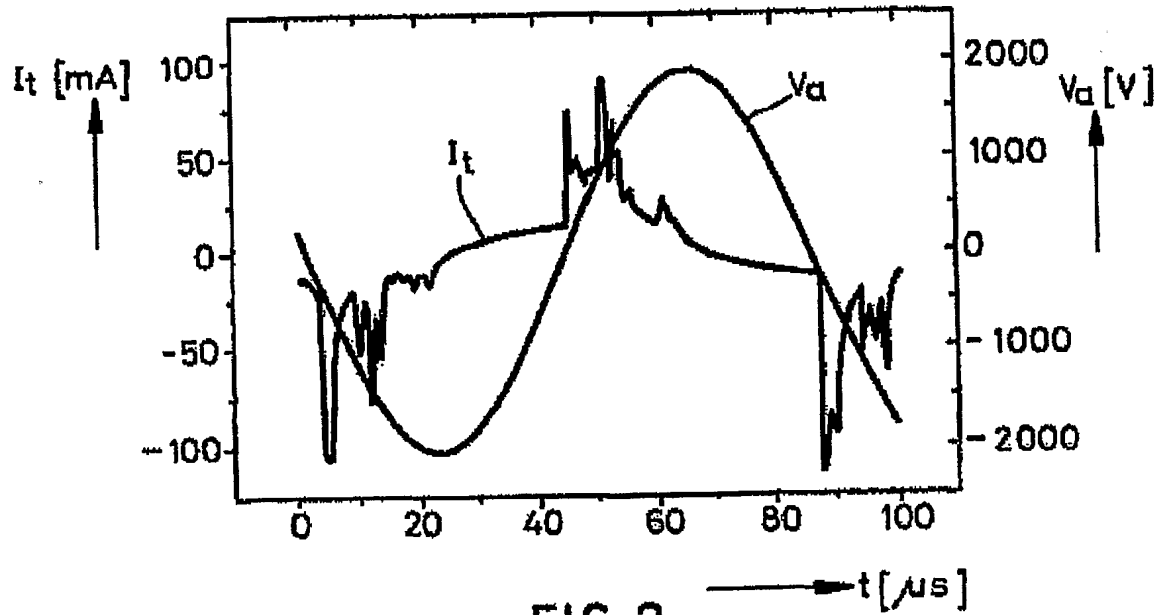


FIG. 2

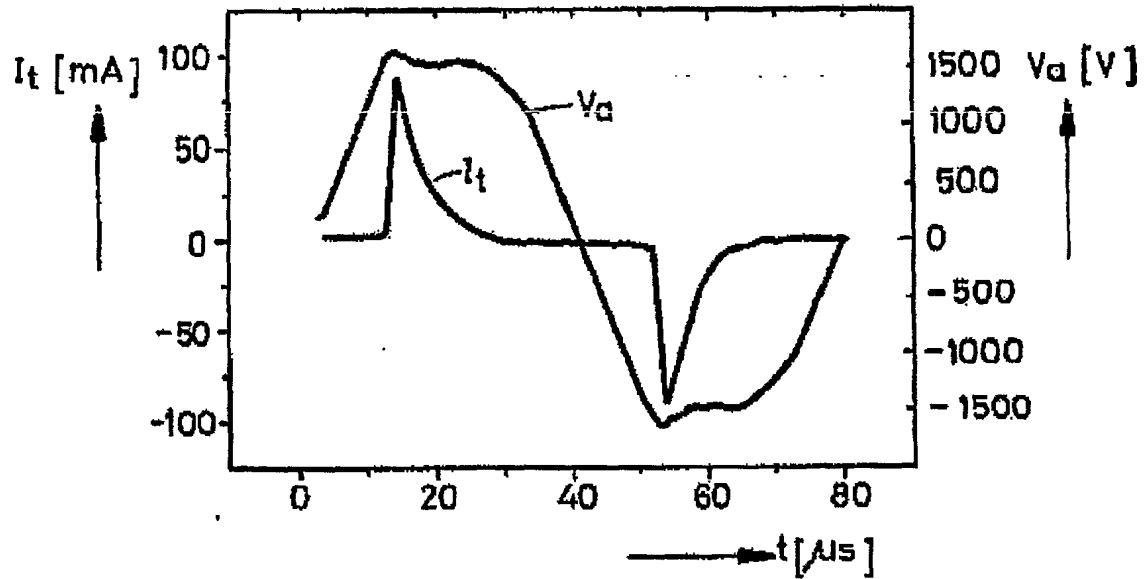


FIG. 3

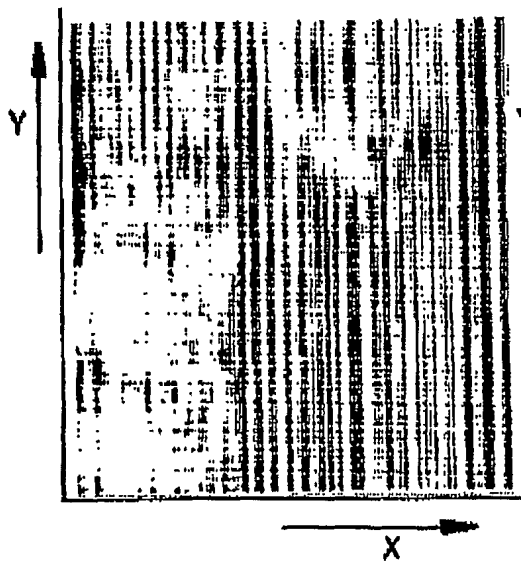


FIG. 4

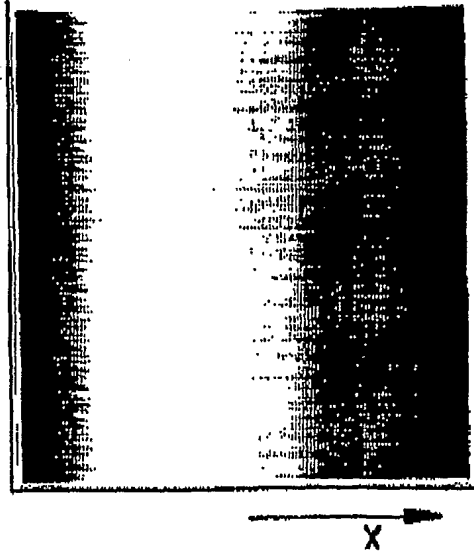


FIG. 5

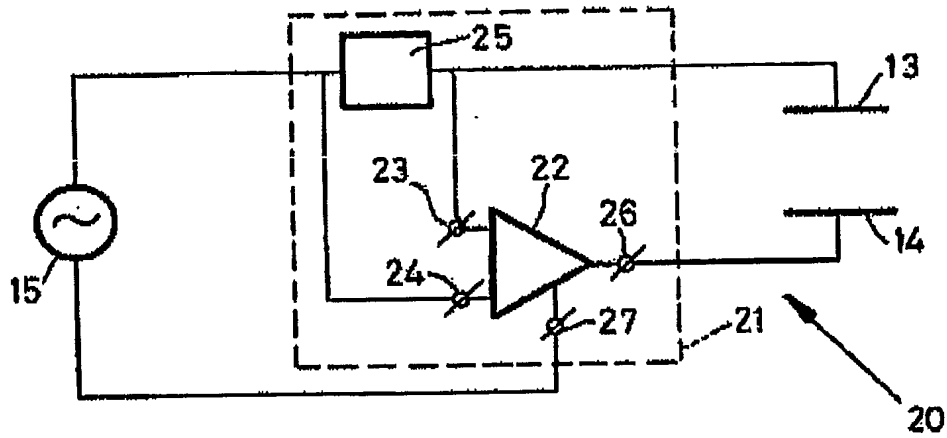


FIG. 6

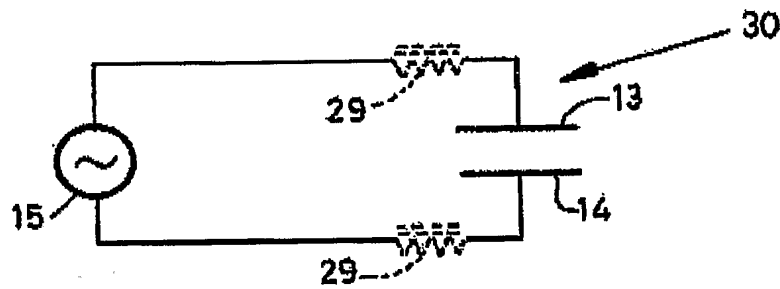


FIG. 7

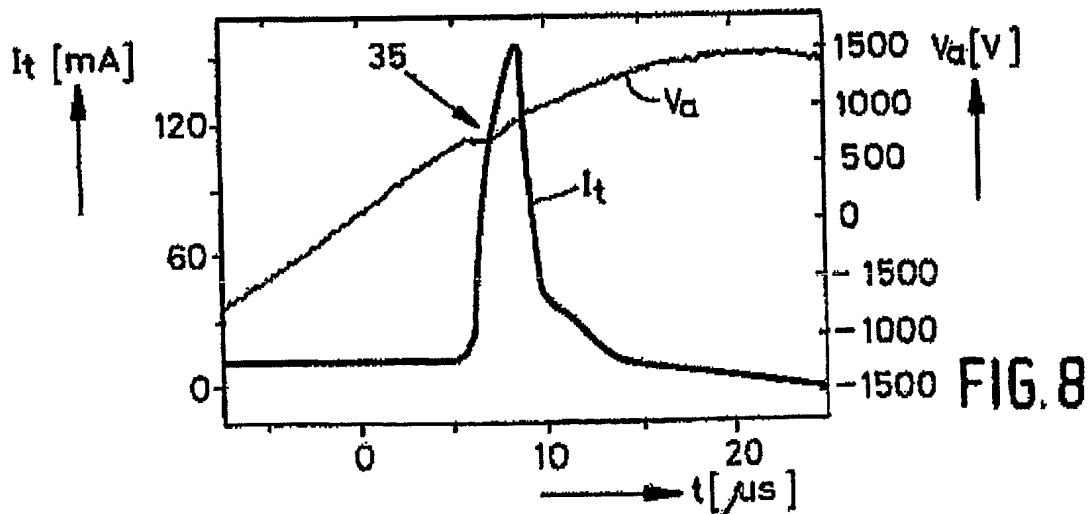


FIG. 8

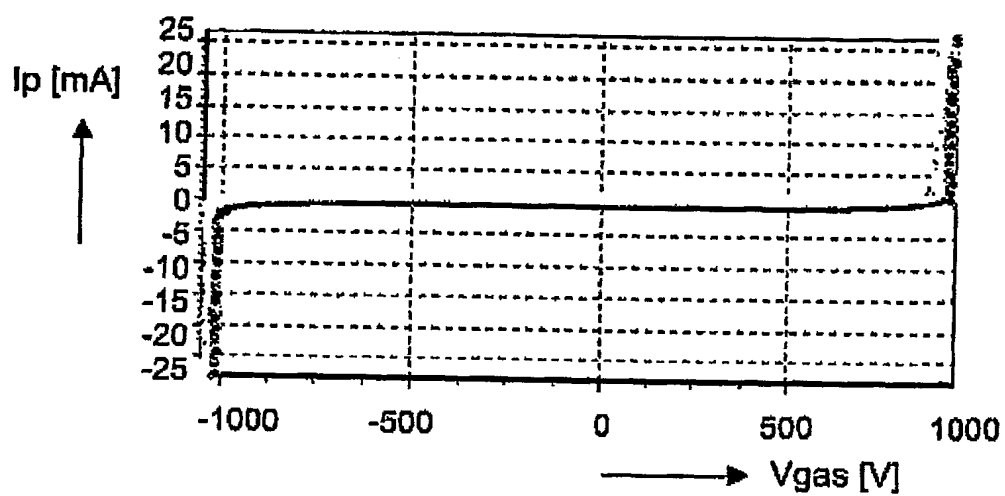


Fig. 9